INDO/S CALCULATIONS ON SIMPLE SILICON COMPOUNDS AND SOME SILICON ORGANIC MOLECULES

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Received May 11th, 1981

The INDO/S method has been extended to silicon-containing systems. On the basis of test calculations for SiH₂, SiHCl, SiF₂, SiH, SiN, SiO⁺, SiF and SiO we suggest the following semiempirical parameters: $\beta_{S1}^0 = -4 \text{ eV}$ and $\gamma_{S1} = 5 \cdot 5 \text{ eV}$. Additional molecules treated are SiH⁺, SiS, SiCC, SiCSi, SiCl, SiCl₂, SiO₂, HNSi, and vinyl- and phenylsilane. Comparison is made with the corresponding carbon species CH₂, CF₂, CCl₂, CH⁺, CO, CS, CH, CF, CN, CO⁺, CO₂, C₃ and benzene. The method with the suggested Si parameter set is employed for the investigation of the electronic structure and electronic spectra of unstable molecules of sila-ethylene, silylimethylene, methylsilylene, disilylene, silylisilylene and silabenzene.

Study of electronic spectra of Si-containing compounds is topical for several reasons. Short-lived low-valent silicon compounds play an important role in reactions at high temperatures and in the interstellar space¹. For example, SiH has been detected in the solar photosphere and the absorption of some N-type stars in the blue-green region was proved¹ to be due to SiCC. Also a possible existence of SiO₂ in the interstellar space is the subject of interest², though SiO₂ is not known to exist under normal conditions. The problem met in the organo-silicon chemistry is the absence of stable compounds with multiple bonds of the $p_{\pi}-p_{\pi}$ -type, in spite of considerable effort to synthesize them (for a recent review see ref.³). Particularly, the prototype compounds silaethylene and silabenzene were the subject of numerous experimental^{4,43,44} and theoretical studies (see papers⁵⁻⁸ and reference therein). As to silicon-containing solids, silica, silicates and alumosilicates belong to the most common materials on the earth (actually Si is the second most common element after oxygen) and a lot of spectroscopic and experimental material about their electronic structure has been accumulated (see for example ref.⁹). Moreover materials as SiO₂ and Si became very popular in electronics¹⁰ in the last years. Among the stable organo-silicon compounds we only note the siloxanes because of their wide technical application as polymeric silicones¹¹.

Difficulties in obtaining experimental information for short-lived low-valent silicon-containing species and silicon-organic intermediates and also a need for

theoretical interpretation of electronic and photoelectron spectra of stable inorganic and organic compounds resulted in a strong demand for theoretical models in this field. Quantum-chemical all-valence electron methods involving spectroscopic parameters are particularly suitable for this purpose because they provide a link between accurate *ab initio* calculations, which are only feasible for small systems, and π -electron methods which are rather limited in their applicability. All-valence electron methods can be applied without technical difficulties to systems with approximately up to 150 atomic orbitals and 50 atoms (40 heavy atoms). This means that rather large conjugated molecules (silabenzene, phenylsilane) and molecular clusters modelling SiO₂, such as Si₆O₁₈H₁₂ or Si(OSi(OH)₃)₄, can be easily treated. Unfortunately within the CNDO/S-INDO/S scheme^{12,13} which is still successfully employed for calculations of electronic spectra, photoelectron spectra and nuclear screening constants in NMR spectroscopy parameters are available only for H, C, N, O (ref.¹²), B, F (ref.^{14,15}), Al (ref.¹⁶), S (ref.¹⁷) and Cl (ref.¹⁵). We considered it therefore expedient to try to suggest semiempirical parameters for silicon. For this purpose we selected a set of small species for which the electronic transition energies are known from experiment and/or ab initio calculations. The set comprises SiH₂, SiHCl, SiF₂, SiH, SiN, SiO⁺, SiF, SiO. We followed the procedure used previously for adjusting the parameters¹⁶ for Al. That means that the parameters searched for, y and β^0 (one-center repulsion integral and bonding parameter) were varied in a range which is reasonable with respect to parameters for the neighbouring atoms in the periodic system. The parameter set reproducing best the reference data was then applied in calculations to further silicon species: SiH⁺, SiS, SiC₂, Si₂C, SiCl, SiCl₂, SiO₂, HNSi, silaethylene, silylmethylene, methylsilylene, disilylene, silylsilylene, silabenzene, and vinyl- and phenylsilane. As in previous treatments of S-containing¹⁷ and Cl-containing¹⁵ systems, the calculations were performed without d-functions on silicon. Some authors claim^{18,19} that the $(p-d)_{\pi}$ overlap is important in silicon chemistry, but recent ab initio calculations²⁰ suggest that its effect in C-Si and O-Si bonds is negligible.

Details of Calculations

The theoretical approach used may be viewed as the original CNDO/S method of Del Bene and Jaffé¹² into which the INDO approximation was incorporated¹³. Extension of the method to second row elements was made consistently with our previous paper¹⁶. In calculations for the determination of β_{si}^0 and γ_{si} parameters we assumed the values of -4, -5 and -6 eV for β_{si}^0 and 4.5, 5.5 and 6.5 for γ_{si} . The ranges into which a reasonable choice of the two parameters should fall, were guessed from the trends of CNDO/S parameters reported for other elements. The best combination appeared to be $\beta_{si}^0 = -4$ eV and $\gamma_{si} = 5.5$ eV which was then used throughout.

The calculations were performed mostly for the experimental geometries. These were available¹ for SiH⁺, SiH, SiN, SiO⁺, SiO, SiF, SiS, SiCl, SiH₂, SiF₂ and SiHCI. For SiCl₂, SiCC and SiCSi we assumed the optimum geometries given by *ab initio* SCF calculations. The basis set used was $4 - 31G^{21,22}$. The following geometry parameters were obtained (bond lengths in 10^{-10} m, bond angles in degrees): SiCC, R(SiC) = 1-688, R(CC) = 1-266, $\ll(SiCC) = 180$; SiCSi, R(SiC) = 1-674, $\ll(SiCSi) = 180$; SiCl₂, $R(SiC) = 2\cdot25$, $\ll(CSiC) = 98\cdot7$. For the following compounds the *ab initio* optimum geometries were taken from the references given in parenthesis: Vinylsilane (ref.²⁰), silaethylene and silabenzene (ref.⁶), H₃CSiH and H₃SiCH (ref.⁸); Si₂H₄ and H₃SiCH (ref.²²), SiO₂ (ref.²) and HNSi (ref.²³). For phenylsilane a standard geometry with R(SiC) = 1-483, $R(CC) = 1\cdot397$, $R(SiH) = 1\cdot48$ and $R(CH) = 1\cdot084$, 10^{-10} m was used. For the purpose of comparison of the results obtained for Si-containing compounds with the data for the corresponding carbon compounds we also performed the INDO/S calculations for the following systems (for the geometries used see the references in parentheses): CH⁺ (ref.²⁴), CN (ref.²⁴), CO (ref.²⁴), CS (ref.²⁴), CH₂ (ref.²⁵), CF₂ (ref.²⁶), CO₂ (ref.²⁵), CCl₂ (ref.²⁵), GCl₂ (ref.²⁵), GCl₂ (ref.²⁵), and benzene (experimental geometry, $R(CC) = 1\cdot397$, $R(CH) = 1\cdot084 \cdot 10^{-10}$ m).

RESULTS AND DISCUSSION

The INDO/S approach was preferred to the CNDO/S method, because the neglect of one-center exchange integrals in the latter may lead in some instances to equal energies for states of different multiplicity (*e.g.* singlet and triplets belonging to the same electronic configuration). Some restrictive features, however, are inherent to both CNDO/S and INDO/S calculations. Particularly it should be recalled that Rydberg states and doubly excited states cannot be accounted for. Since small molecules can be treated accurately by *ab initio* calculations, the principal utility of semiempirical calculations of the INDO/S type may be found in their applications to larger systems. Having this in mind we performed first a series of calculations for small molecules to test the parameter set adopted and then we performed calculations for larger systems (*vide infra*) for which accurate *ab initio* calculations are hardly feasible.

Spectra of Small Molecules and Radicals

The results are presented in Tables I - VIII. We considered it useful to present also the results for the corresponding carbon (Table V) and aluminum compounds (Table VI) to see whether the differences between the predicted and observed transition energies in the silicon compounds are due to a poor Si parameter set or due to deficiencies in the theoretical approach itself.

Table I shows the results for divalent silicon compounds. With SiH_2 the transition energy was determined experimentally only for the $A^{-1}B_1$ state. The greatly overestimated prediction for this transition energy may be partly due to a great change in the bonding angle HSiH upon excitation ($123^{\circ} \leftarrow 92^{\circ}$). The vertical experimental transition energy may therefore be considerably higher than the T_0

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TABLE 1

Transition energies (in 10³ cm⁻¹) for SiH₂, SiF₂, SiHCl, and SiCl₂

Molecule	State	Main configuration ^a	Calc. INDO/S	Observed ^b	Calc. ab initio
SiH ₂	$X^{1}A_{1}$	$4a_1^2 2b_2^2 5a_1^2$	0	0	
2	${}^{3}B_{1}$	$4a_1^22b_2^25a_1^2b_1$	12.9		0
	$A^{1}B_{1}$	$4a_1^2 2b_2^2 5a_1^2 b_1$	23.3	15.5	12-0 ^c
	${}^{3}A_{2}$	$4a_1^2 2b_2 5a_1^2 2b_1$	27.1		
	${}^{3}A_{1}$	$4a_1^2 2b_2^2 5a_1 6a_1$	28.7		
	${}^{1}A_{2}$	$4a_1^2 2b_2 5a_1^2 2b_1$	29.0		
	${}^{3}B_{2}$	$4a_1^2 2b_2^2 5a_1 3b_2$	30.3		
	$^{1}A_{1}$	$4a_1^2 2b_2^2 5a_1 6a_1$	41.7		
	${}^{3}B_{2}$	$4a_1^2 2b_2 5a_1^2 6a_1$	41.9		
	${}^{3}A_{1}$	$4a_1^2 2b_2 5a_1^2 3b_2$	43-3		
	${}^{1}B_{2}$	$4a_1^2 2b_2^2 5a_1 3b_2$	45.8		
SiF ₂	$X^{1}A_{1}$	$7a_1^21a_2^25b_2^28a_1^2$	0	0	0
	${}^{3}B_{1}$	$7a^2 1a^2 5b^2 8a, 3b$	17.1	26.3	25·9ª
	$A^{1}B_{1}$	741742552541551	31.1	44.1	47·8ª
	${}^{3}A_{1}$	$7a_1^21a_2^25b_2^28a_19a_1$	49.9		
	${}^{3}B_{2}$	$7a_1^21a_2^25b_2^28a_16b_2$	50.6		53·3ª
	$^{3}A_{2}$	$7a_1^2 1a_2^2 5b_2 8a_1^2 3b_1$	52.3		$70 \cdot 4^a$
	A_2	2 2 2	53-1		
	$^{3}B_{2}$	$7a_1^21a_25b_2^28a_1^23b_1$	54.3		
	A_1	$7a_1^21a_2^25b_2^28a_19a_1$	58-4		
	B_2	$7a_1^21a_25b_2^28a_1^23b_1$	59-0		80·9"
	$^{3}A_{1}$	$2b_17a_1^21a_2^25b_2^28a_1^23b_1$	60.5		
	$\begin{bmatrix} B_1 \\ 1 \end{bmatrix}$	$7a_1 1a_2^2 5b_2^2 8a_1^2 3b_1$	60.5		
	B_1		62.5		
	^A 2	$4b_22b_1^27a_1^21a_2^28a_1^23b_1$	64.7		
	^A2J	7 1 25120 201	65.9	(2.2	70.14
	<i>B</i> ₂	1a11a25026a1602	07.0	62.3	79.1
SiCl ₂	$X^{1}A_{1}$	$3b_1^2 2a_2^2 8b_2^2 11a_1^2$	0	0	
	$^{3}B_{1}$	$3b_1^2 2a_2^2 8b_2^2 11a_1 4b_1$	15.2		
	$^{3}A_{1}$	$3b_1^2 2a_2^2 8b_2^2 11a_1 12a_1$	21.1		
	$^{3}B_{2}$	$3b_1^2 2a_2^2 8b_2^2 11a_19b_2$	22.3		
	$A^{T}B_{1}$	$3b_1^2 2a_2^2 8b_2^2 11a_1 4b_1$	23.4	30.0	
	$^{3}A_{2}$	$3b_1^2 2a_2^2 8b_2 11a_1^2 4b_1$	27.6		
	(A_2)		28.4	(28.3)	
	B_2	$3b_1^2 2a_2^2 8b_2 11a_1^2 12a_1$	28.2		
	A_1	$3b_1^2 2a_2^2 8b_2 11a_1^2 9b_2$	29.0		
	³ A ₂	$3b_1^2 2a_2 8b_2^2 11a_1^2 12a_1$	29.3		
	B_1	$3b_1 2a_2^2 8b_2^2 11a_1^2 12a_1$	29.5		
	^A ₁	$3b_1^2 2a_2^2 8b_2^2 11a_1 12a_1$	30.5		
	B_2	$3b_1^2 2a_2^2 8b_2 11a_1^2 12a_1$	30.8		

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(Continued)

Molecule	State	Main configuration ⁴	Calc. INDO/S	Observed ^b	Calc. ab initio
	$^{1}A_{2}$	$3b_1^2 2a_2 8b_2^2 11a_1^2 12a_1$	31.9		
	B_1	$3b_12a_2^28b_2^211a_1^212a_1$	32.1		
	$\begin{pmatrix} {}^{3}B_{2} \\ {}^{1}B_{2} \end{pmatrix}$	$3b_1^2 2a_2 8b_2^2 11a_1^2 4b_1$	32·1 32·2		
	$\begin{bmatrix} {}^{3}A_{1}\\ {}^{1}A_{1} \end{bmatrix}$	$3b_12a_2^28b_2^211a_1^24b_1$	33·1 33·2		
SiHCl	$X^{1}A'$	$(3a'')^2(12a')^2(13a')^2$	0	0	
	$A^{1}A''$	$(3a'')^2(12a')^213a'4a''$	21·1 20·7	21.6	
	$^{3}A'$	$(3a'')^2(12a')^213a'14a'$	22.8		
	³ A'	$(3a'')^2(12a')^213a'15a'$	27.0		
	${}^{3}A''$	$(3a'')^2 12a'(13a')^2 4a''$	30.9		
	$^{1}A'$	$(3a'')^2(12a')^213a'14a'$	31.3		
	${}^{1}A''$	$(3a'')^2 12a'(13a')^2 4a''$	32.2		
	$^{3}A'$	$(3a'')^2 12a'(13a')^2 14a'$	32.8		
	${}^{3}A''$	$3a''(12a')^2(13a')^214a'$	34.5		
	$^{3}A'$	$3a''(12a')^2(13a')^24a''$	34.7		
	$^{1}A'$	$3a''(12a')^2(13a')^24a''$	35.7		
	${}^{1}A''$	$3a''(12a')^2(13a')^214a'$	37.1		
	${}^{3}A'' \\ {}^{1}A'' $	$11a'(3a'')^2(12a')^2(13a')^24a''$	37·5 38·4		

^a Inner shells accounted for; ^b T_0 from ref.¹; ^c ${}^1B_1 - {}^3B_1$ difference, ref.²⁸; ^d ref.²⁹; essentially *double zeta* basis set.

energy. The data for CH₂ show the same trend (Table V) which suggests that the overestimation of the $A^{1}B_{1} \leftarrow X^{1}A_{1}$ transition energy for SiH₂ is not due to a poor Si parameter set. Determination of the spin multiplicity of the ground state of SiH₂ is difficult. As with CH₂, it may be profitable²⁸ for this purpose to know the ${}^{1}B_{1} - {}^{3}B_{1}$ energy difference. Our prediction is 10 400 cm⁻¹, in good agreement with the result of *ab initio* calculations^{28,29} (12 000 cm⁻¹). Also the INDO/S result for the AlH₂ (Table VI) may be noted, since in both SiH₂ and AlH₂ the $2b_{1} \leftarrow 5a_{1}$ transition is involved. A somewhat lower transition energy of 20 500 cm⁻¹ predicted¹⁶ for AlH₂ corresponds well to a somewhat lower experimental value for AlH₂ with upper limit of 15 200 cm⁻¹. For SiF₂ three excited states are experimentally known. Their casignment and the order of transition energies are supported by the present calculations. The difference between the predicted and observed ${}^{1}B_{1} \leftarrow {}^{1}A_{1}$ transitions

(13 000 cm⁻¹) is large but it is also met with CF₂ (7 300 cm⁻¹, see Table V). As with SiH₂, the singlet-triplet splitting is well reproduced. The predicted value is 14 100 cm⁻¹, compared to the observed one of 17 800 cm⁻¹. The only state of HSiCl observed spectroscopically is $A^{-1}A''$. Its transition energy is well reproduced by our calculations. For SiCl₂ two excited states were observed in emission in the region at 30 000 cm⁻¹. The assignment of $A^{-1}B_1$ to one of them is confirmed by our calculation, though the transition energy is somewhat underestimated. (This is also the case with Si₂F₂ and CF₂, see Table V.) The ${}^{-1}B_1 - {}^{-3}B_1$ splitting is predicted to be 8 200 cm⁻¹ INDO/S gives for this silylene a large number of low-lying states. Eight triplet states

TABLE II Transition energies (in 10^3 cm⁻¹) in SiO and SiS

Malassila	State	Main	Calc.	01	ab in	itio
Molecule	State	configuration ^b	INDO/S	Observed	ab ini d 0 27-6 31-8 30-7 32-5 33-4 33-1 40-9 61-8 53-9 58-5 59-8	е
SiO	$X^{1}\Sigma^{+}$	$6\sigma^2 2\pi^4 7\sigma^2$	0	0	0	0
	$a^{3}\Sigma^{+}$	$6\sigma^2 2\pi^3 7\sigma^2 3\pi$	22.0	33-4	27.6	38.0
	b ³ П,	$6\sigma^2 2\pi^4 7\sigma 3\pi$	21.1	33.9	31.8	36.0
	$d^{3}\Delta_{r}$	$6\sigma^2 2\pi^3 7\sigma^2 3\pi$	25.3	36.5	30.7	42.0
	$e^{-3}\Sigma^{-}$	$6\sigma^2 2\pi^3 7\sigma^2 3\pi$	28.5	38.3	32.5	43.5
	$C^{1}\Sigma^{-}$	$6\sigma^2 2\pi^3 7\sigma^2 3\pi$	28.5	38.6	33.4	45.0
	$D^{-1} \varDelta$	$6\sigma^2 2\pi^3 7\sigma^2 3\pi$	31.6	38.8	33.1	45.7
	$A^{-1}\Pi$	$6\sigma^2 2\pi^4 7\sigma 3\pi$	27.8	42.8	40.9	45.4
			(43·7) ^f			
	$E^{1}\Sigma^{+}$	$6\sigma^2 2\pi^4 7\sigma 8\sigma$	52.4	52.9	61.8	
	³ <i>Π</i> ,	$6\sigma 2\pi^4 7\sigma^2 3\pi$	47.3	_	53.9	
	${}^{3}\Sigma^{+}$	$6\sigma^2 2\pi^4 7\sigma 8\sigma$	57.0	57.5	58.5	
	$c^{-3}\Pi_{i}$	$6\sigma^2 2\pi^3 7\sigma^2 8\sigma$	59.2	59.3	59·8	
SiS	$X^{1}\Sigma^{+}$	$8\sigma^2 3\pi^4 9\sigma^2$	0	0		
	${}^{1}\Sigma^{-}$	$8\sigma^2 3\pi^3 9\sigma^2 4\pi$	14.9			
	$D^{1}\Pi$	$8\sigma^2 3\pi^4 9\sigma 4\pi$	16.5	34.9		
			$(32.4)^{f}$			
	¹ ⊿	$8\sigma^2 3\pi^3 9\sigma^2 4\pi$	16.7			
	$E^{-1}\Sigma^+$	$8\sigma^2 3\pi^4 9\sigma 10\sigma$	25.1	41· 7		
	$^{1}\Pi$	$8\sigma^2 3\pi^3 9\sigma^2 10\sigma$	28.6			

^{*a*} For SiO see ref.³⁰; ^{*b*} Inner shells accounted for; ^{*c*} T_e for SiO from ref.³⁰, T_0 for SiS form ref.¹; ^{*d*} ref.³⁰; ^{*e*} From ref.³¹, values include corrections based upon the adaption of calculated values to experimental data for CO; ^{*f*} In parenthesis the energy is given which is corrected by the difference between the experimental energy for the $A^{1}II$ state of CO and the INDO/S calculation (see also Fig. 1).

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are predicted to lie below 30 000 cm⁻¹. Among the singlet states, the ${}^{1}A_{2}$ and ${}^{1}A_{1}$ states lie very close to the observed second state.

Table II presents the results for the diatomic molecules SiO and SiS. The experimental data available for SiO have already been analyzed in detail by means of *ab initio* calculations³⁰. A comparison made in the cited paper³⁰ is supplemented in Table V for our INDO/S results. The overall order of the states in SiO is well reproduced. Particularly, the predicted locations of low-lying triplet states $a^{-3}\Sigma^+$, $b^{-3}\Pi$ and $d^{-3}A$ agree well with the experimental and *ab initio* data. The next three states, $e^{-3}\Sigma^-$, $C^{-1}\Sigma^-$ and $D^{-1}A$, are predicted incorrectly to lie above the $A^{-1}\Pi$ state, but for the states that lie considerably higher than the $A^{-1}\Pi$ state, the agreement between INDO/S and experiment is almost quantitative. Experimentally, the best known state of SiO is the $A^{-1}\Pi$ state, A large difference between the observed and INDO/S transition energies (15 000 cm⁻¹) is also met with the corresponding transition in CO (15 800 cm⁻¹), CS and SiS (see Tables II and V). Fig. 1 shows clearly that the observed trend of decreasing ${}^{1}\Pi \leftarrow {}^{1}\Sigma^{+}$ transition energies in the series CO–SiO–CS–-SiS is perfectly reproduced.

The results for the diatomic radicals, SiH, SiN, SiO⁺, SiF and SiCl, are collected in Table III. In SiH the three states arising from the $4\sigma^25\sigma2\pi^2$ configuration, A^2A , ${}^2\Sigma^-$, $B^2\Sigma^+$, are very similar to the corresponding states of CH (Table V). Table III shows that the INDO/S calculations are in agreement with both the experimental values and the *ab initio* calculations. Compared to experiments, the predicted D^2A and $E^2\Sigma^+$ states are too high by 15 000 cm⁻¹. For the predicted ²II states there is no experimental evidence. They should lie between the $B^2\Sigma^+$ and D^2A states and they should be both mainly due to the $5\sigma \rightarrow 6\sigma$ transition. In agreement with experiment, INDO/S predicts for the two isoelectronic species SiN and SiO⁺ the



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TABLE III

Doublet transition energies (in 10³ cm⁻¹) for SiH, SiN, SiO⁺, and SiF

Radical	State	Main configuration ^a	Calcd. $(f. 10^3)$ INDO/S	Observed ^b	ab initio
SiH	$\begin{array}{c} \chi^2 \Pi \\ C^2 \Sigma^+ \\ \chi^2 \Lambda \end{array}$	$4\sigma^2 5\sigma^2 2\pi$ $4\sigma^2 5\sigma^2 6\sigma$ $4\sigma^2 5\sigma^2 \pi^2$	0 21.8 (1) 23.6 (12)	0 30.8 ^g 24.2 ^g	0 25:0 ^c
	2 ₂ -	$4\sigma^{2}5\sigma^{2}\pi^{2}$	26.2 (12)	242	25 0 26.8°
	$B^2\Sigma^+$	$4\sigma^2 5\sigma 2\pi^2$	28.0 (14)	30-8 ^g	31.99
	² Π	$4\sigma^2 5\sigma 2\pi 6\sigma$	34.2 (1)		
	² П	$4\sigma^2 5\sigma 2\pi 6\sigma$	54.1 (295)		
	$D^2 \Delta$	$4\sigma 5\sigma^2 2\pi^2$	64.9 (71)	48.5 ^g	
	$E^{2}\Sigma^{+}$	$4\sigma 5\sigma^2 2\pi^2$	69.4 (78)	52·4 ^g	
	² <i>Σ</i> ⁻	$4\sigma 5\sigma^2 2\pi^2$	80.6 (338)		
SiN	$X^{2}\Sigma^{+}$	$6\sigma^2 2\pi^4 7\sigma$	0	0	
5	2П	$6\sigma^2 2\pi^3 7\sigma^2$	0.1		
	$B^2\Sigma^+$	$6\sigma^2 2\pi^3 7\sigma 3\pi$	15.6	24.2	
	² <i>Σ</i> ⁻	$6\sigma^2 2\pi^3 7\sigma 3\pi$	17.1		
	² <i>Δ</i>	$6\sigma^2 2\pi^3 7\sigma 3\pi$	19.0		
	² ⊿	$6\sigma^2 2\pi^3 7\sigma 3\pi$	20.9		
	² П	$6\sigma^2 2\pi^4 3\pi$	22.4		
	${}^{2}\Sigma^{-}$	$6\sigma^2 2\pi^3 7\sigma 3\pi$	22.8		
	${}^{2}\Sigma^{+}$	$6\sigma 2\pi^4 7\sigma^2$	34.8		
	² П	$6\sigma^2 2\pi^3 7\sigma 8\sigma$	39.3		
	${}^{2}\Sigma^{+}$	$6\sigma^2 2\pi^4 8\sigma$	40.4	50.3	
	² П	$6\sigma 2\pi^4 7\sigma 3\pi$	52.5		
SiO ⁺	$X^2 \Sigma^+$	$6\sigma^2 2\pi^4 7\sigma$	0	0	
	$A^2\Pi$	$6\sigma^2 2\pi^3 7\sigma^2$	3.6 (0.4)	_	
				(4·7) ^d	
	$B^2\Sigma^+$	$6\sigma 2\pi^4 7\sigma^2$	20.9 (56.1)	30.5	
				(25·7) ^d	
	² <i>П</i>	$6\sigma^2 2\pi^4 3\pi$	35.6 (7.8)		
	${}^{2}\Sigma^{-}$	$6\sigma^2 2\pi^3 7\sigma 3\pi$	38.5		
	2⊿	$6\sigma^2 2\pi^3 7\sigma 3\pi$	40.7		
	${}^{2}\Sigma^{+}$	$6\sigma^2 2\pi^3 7\sigma 3\pi$	43.1 (5.7)		
	2⊿	$6\sigma^2 2\pi^3 7\sigma 3\pi$	44.5		
SiF	Х ² П.	$2\pi^4 7\sigma^2 3\pi$	0	0	
	$A^{2}\Sigma^{+}$	$2\pi^4 7\sigma^2 8\sigma$	32.4 (0.0)	22.8	
	C ² ⊿	$2\pi^4 7\sigma 3\pi^2$	35.1 (38)	39-5	
	$B^2\Sigma^+$	$2\pi^{4}7\sigma^{3}\pi^{2}$	39.8	34·6 ^e	
	$D^{2}\Sigma^{-}$	$2\pi^4 7\sigma 3\pi^2$	45-7	47·5 ^e	
	2П	$2\pi^{3}7\sigma^{2}3\pi^{2}$	57.0		
	² Ø	$2\pi^{3}7\sigma^{2}3\pi^{2}$	59.3		
	2Л	$2\pi^{3}7\sigma^{2}3\pi^{2}$	62.4		
	² Л	$2\pi^3 7\sigma^2 3\pi^2$	64-3		

INDO/S Calculations on Simple Silicon Compounds

1	1	5	7
	×	-	1

I ABLE III

(Continued)

Radical State con		Main configuration ^a	Calcd. (f . 10 ³) INDO/S	Observed ^b	ab initio
SiCl	Х ² П	$3\pi^4 9\sigma^2 4\pi^1$	0	0	
	$A^{2}\Sigma^{+}$	$3\pi^4 9\sigma^2 10\sigma$	13.5	23·0 ^f	
	$C^2 \Delta$	$3\pi^4 9\sigma 4\pi^2$	28.2	41·2 ^f	
	$B^2 \Sigma^-$	$3\pi^4 9\sigma 4\pi^2$	29.9	34.15	
	${}^{2}\Sigma^{+}$	$3\pi^4 9\sigma 4\pi^2$	32.4		
	² П	$3\pi^49\sigma 4\pi 10\sigma$	33.1		
	² П	$3\pi^3 9\sigma^2 4\pi^2$	35.3		
	$^{2}\Sigma$	$3\pi^3 9\sigma^2 4\pi 10\sigma$	36.8		
	² ⊿	$3\pi^3 9\sigma^2 4\pi 10\sigma$	37.1		
	² П	$3\pi^{3}9\sigma^{2}4\pi^{2}$	38.4		
	$^{2}\Phi$	$3\pi^3 9\sigma^2 4\pi^2$	38.8		
	$^{2}\Sigma$	$3\pi^2 9\sigma^2 4\pi 10\sigma$	39.2		
	² ⊿	$3\pi^3 9\sigma^2 4\pi 10\sigma$	39.7		
	$^{2}\Sigma$	$3\pi^3 9\sigma^2 4\pi 10\sigma$	40.0	-	
	² П	$3\pi^3 9\sigma^2 4\pi^2$	42.7		

^a Inner shells accounted for; ^b T_0 from ref.¹; ^c ref.³², basis set (Si 6s, 3p; H 1s); ^d Values estimated from the photoelectron spectrum of SiO, ref.³³; ^e Probably Rydberg states; ^f T_e values from ref.²⁴; ^g T_0 values from ref.³⁴.

TABLE IV

Comparison of calculated and observed energies for the lowest allowed transition in C_3 , SiCC and SiCSi (in 10³ cm⁻¹)

Molecule	Geometry	State	Main configuration	INDO/S	Observed
CCC	$D_{\infty h}$ (exp.)	$\begin{array}{c} X {}^{1}\Sigma_{g}^{+} \\ A {}^{1}\Pi_{u} \end{array}$	$(4\sigma_{g}^{+})^{2}1\pi_{u}^{4}(3\sigma_{u}^{+})^{2} (4\sigma_{g}^{+})^{2}1\pi_{u}^{4}(3\sigma_{u}^{+})^{1}1\pi_{g}^{1}$	0 18·4	0 24·7 ^a
SiCC	$C_{\infty v}^{d}$	$\begin{array}{c} X {}^{1} \Sigma^{+} \\ A {}^{1} \Pi \end{array}$	$8\sigma^2 2\pi^4 9\sigma^2$ $8\sigma^2 2\pi^4 9\sigma^1 3\pi^1$	0 11·3	0 20·1ª
SiCSi	$D_{\infty h}^{d}$	$\begin{array}{c} X {}^{1}\Sigma_{g}^{+} \\ A {}^{1}\Pi_{u} \end{array}$	$\frac{(6\sigma_{g}^{+})^{2}(5\sigma_{u}^{+})^{2}2\pi_{u}^{4}}{(6\sigma_{g}^{+})^{2}(5\sigma_{u}^{+})^{1}2\pi_{u}^{4}2\pi_{g}^{1}}$	0 12·8	0 18·9 ^b 19·3 and 19·9, resp. ^c

^a T₀ value from ref.²⁵, ^b In Ar matrix, refs^{1,40}, ^c In Ne matrix, refs^{1,40}, ^d Geometry optimization employing 4-316 *ab initio* SCF method.

TABLE V

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Comparison of excitation	energies (in	10^{3} c	m ⁻¹)	between	silicon	and t	the c	orresponding	carbon
compounds									

General	m 111		Experime	ent	Calcu	lation (IN	NDO/S)
formula	Transition	Si ^a	С	difference	Si	С	difference
AH^+	${}^{1}\Pi \leftarrow {}^{1}\Sigma^{+}$	25.0	23·6 ^b	1.4	24.1	24.6	- 0.5
AH	$^{2}\Delta \leftarrow ^{2}\Pi$	24.2	$23 \cdot 2^{b}$	1.0	23.6	25·3ª	- 1.7
	$^{2}\Sigma^{+} \leftarrow ^{2}\Pi$	30.8	$31 \cdot 8^{b}$	- 1.0	28.0	34·3ª	6.3
AH ₂	${}^{1}B_{1} \leftarrow {}^{1}A_{1}$	15.5	7·1e	8.4	23.3	16.7	6.6
AN	${}^{2}\Sigma^{+} \leftarrow {}^{2}\Sigma^{+}$	24.2	$25 \cdot 8^{b}$	- 1.6	15.6	31.4	-15.8
AO^+	$^{2}\Pi \leftarrow ^{2}\Sigma^{+}$	(4·7) ^g	$20 \cdot 4^{b}$	(-15.7)	3.6	29.5	- 25.9
	${}^{2}\Sigma^{+} \leftarrow {}^{2}\Sigma^{+}$	30.5	45.6^{b}	-15.1	20.9	43.9	-23.0
AF	$^{2}\Sigma^{+} \leftarrow ^{2}\Pi$	22.8	53.6 ^c	- 30.8	32.4	51·7 ^d	- 19.3
AO	${}^{1}\Pi \leftarrow {}^{1}\Sigma^{+}$	42.6	64.7^{b}	- 22·1	27.9	49.3	-21.4
AS	${}^{1}\Pi \leftarrow {}^{1}\Sigma^{+}$	34.9	$38 \cdot 8^{b}$	- 4.0	16.5	21.0	- 4.5
AF ₂	${}^{1}B_{1} \leftarrow {}^{1}A_{1}$	44.1	$37 \cdot 7^e$	6.4	31.1	30.4	0.7
ACl_2	$^{1}B_{1} \leftarrow ^{1}A_{1}$	30.0	30·3 [#]	- 0.3	23.4	19.3	4.1
ACĈ	${}^{1}\Pi \leftarrow {}^{1}\Sigma^{+}$	20.1	24.7^{e}	- 4.6	11.3	18.4	- 7.1
ACA	${}^{1}\Pi_{u} \leftarrow {}^{1}\Sigma_{g}^{+}$	18.9	$24 \cdot 7^e$	- 5.8	12.8	18.4	- 5.6

^a Experimental values (preferably T_0) taken from ref.¹ if not otherwise noted; ^b T_0 from ref.²⁴ ^c For references see the cited paper¹³; ^d ref.¹³; ^e ref.²⁵; ^f For references see the cited paper³⁵; ^g PES for SiO, ref.³³; ^h ref.²⁷.

TABLE VI

Comparison of excitation energies (in 10^3 cm⁻¹) between silicon and aluminum compounds

Orbital		Si	licon			Alur	ninium ^a	
transition	species	observed	INDO/S	difference	species	observed	INDO/S	difference
$2b_1 \leftarrow 5a_1$	SiH2	15.5	23.3	7.8	AlH ₂	<15.2	20.5	< -5.3
$2\pi \leftarrow 5\sigma$	SiH [∓]	25.0	24.1	0.9	AIH	23.8	25.6	-1.8
$7\sigma \leftarrow 2\pi$	SiO ⁺	(4.7)	3.6	1.1	AlO	5.4	0.1	5.5
$3\pi \leftarrow 7\sigma$	SiF	39.5	35.1	4.4	AIF	43.9	39.5	4.4
4π <i>→</i> -9σ	SiCl	41.2	28.2	13.0	AICI	38.2	32.2	6.0

^a INDO/S results taken from ref.¹⁶, for experimental references see the cited paper¹⁶.

ground state to be ${}^{2}\Sigma^{+}$. The ${}^{2}\Pi$ state is calculated to be slightly above the ground state. Although it was not observed directly in the spectra of SiN or SiO⁺, evidence for the existence of such a state can be derived from the photoelectron spectrum³³ of SiO. The difference in ionization potentials of SiO corresponds to the excitation energies of the ionized species (Table III, values in parenthesis). The agreement with the calculated value (3 600 cm⁻¹) is fair. The energy of the $B^{2}\Sigma^{+}$ state, however, is considerably underestimated. The underestimation is almost uniform, being 8 600 cm⁻¹ for SiN and 9 600 cm⁻¹ for SiO⁺. In contrast, the excitation energies of the analog carbon radicals are fairly reproduced or even overestimated (Table V). With SiF the calculation overestimates the first transition by 10 400 cm⁻¹. However a large decrease of this transition energy when compared to CF is qualitatively reproduced (Table V). The symmetry and electron configuration of the $X^{2}\Pi$, $A^{2}\Sigma^{+}$ and $C^{2}\Lambda$ states are in agreement with the conclusions from experiment. The agreement for the C $^{2}\Delta$ transition is rather good. The $^{2}\Sigma^{+}$ and $^{2}\Sigma^{-}$ states arising from the $2\pi^4 7\sigma 3\pi^2$ configuration might be assigned to the states (B and D) observed at 34 600 and 47 500 cm⁻¹. It should be noted, however, that the latter seem to have Rydberg character as suggested by its vibrational frequencies¹. The same also holds for the ${}^{2}\Pi$ states (C' and D') found at 42 000 and 46 700 cm⁻¹ and the G state at 52 000 cm⁻¹. One may expect that the higher valence ${}^{2}\Pi$ states due to the

State	Main configuration	INDO/S (f. 10 ³)	ab initio ^a
¹ Σ ⁺	$7\sigma^2 2\pi^4$	0	0
${}^{3}\Sigma^{+}$	$7\sigma^2 2\pi^3 3\pi$	9.0	~35
³ ⊿	$7\sigma^2 2\pi^3 3\pi$	12.7	
³ Σ ⁻	$7\sigma^2 2\pi^3 3\pi$	16.0	
${}^{1}\Sigma^{-}$	$7\sigma^2 2\pi^3 3\pi$	16.0 (0)	$\sim 40 - 45$
¹ ⊿	$7\sigma^2 2\pi^3 3\pi$	19.2 (0)	
3 ∏	$7\sigma^2 2\pi^4 3\pi$	28.8	
3 ∏	$7\sigma^2 2\pi^3 8\sigma$	34.9	
¹ П	$7\sigma 2\pi^4 3\pi$	40.3 (80)	~ 60
$^{1}\Pi$	$7\sigma^2 3\pi^3 8\sigma$	43.6 (54)	
${}^{1}\Sigma^{+}$	$7\sigma 2\pi^4 8\sigma$	48.3 (166)	
${}^{3}\Sigma^{+}$	$7\sigma 2\pi^4 8\sigma$	50·3	

TABLE VII Calculated transition energies (in 10^3 cm⁻¹) for HNSi

^a Approximate data inferred from ref.²³.

ł		0	=C=0				0Si0
ale	main configuration ^a	observed ^b	observed ^c	ab initio ^d	INDO/S ^e	INDO/S	main configuration
+ 0	$1\pi_{u}^{4}3\sigma_{u}^{2}1\pi_{e}^{4}$	0	0	0	0	0	$2\pi_{u}^{4}4\sigma_{u}^{2}1\pi_{g}^{4}$
1,1	$1\pi_{u}^{4}3\sigma_{u}^{2}1\pi_{g}^{3}2\pi_{u}^{1}$	52-7	60.5	76-0	48-3	42.8	$2\pi_{\rm u}^44\sigma_{\rm u}^21\pi_{\rm g}^33\pi_{\rm u}^1$
4"	$1\pi_{u}^{4}3\sigma_{u}^{2}1\pi_{e}^{3}2\pi_{u}^{1}$	67-8	0.69	76-1	51-1	45-0	$2\pi_{\rm u}^4 4\sigma_{\rm u}^2 1\pi_{\rm g}^3 3\pi_{\rm u}^1$
11	$1\pi_{u}^{4}3\sigma_{u}1\pi_{g}^{4}2\pi_{u}^{1}$	75-0	75-0	73-4	75-7	49-8	$2\pi_{\rm u}^4 4\sigma_{\rm u}^1 1\pi_{\rm g}^4 3\pi_{\rm u}^1$
+ ء لم	$1\pi_{u}^{4}3\sigma_{u}^{2}1\pi_{a}^{3}2\pi_{u}^{1}$	89-4	90.3	60-3 ^g	88-8 (1-28) ^f	55+7 (0-17) ⁵	$2\pi_{\rm u}^4 4\sigma_{\rm u}^1 1\pi_{\rm g}^4 6\sigma_{\rm g}^1$
l a	$1\pi_{\rm u}^3 3\sigma_{\rm u}^2 1\pi_{\rm e}^4 2\pi_{\rm u}^1$				90-8	77-1	$2\pi_{\rm u}^3 4\sigma_{\rm u}^2 1\pi_{\rm g}^4 3\pi_{\rm u}^1$
ۍ م	$1\pi_{u}^{3}3\sigma_{u}^{2}1\pi_{x}^{4}2\pi_{u}^{1}$				94.7	79-5	$2\pi_{u}^{3}4\sigma_{u}^{2}1\pi_{g}^{4}3\pi_{u}^{1}$
ر ح	$1\pi_{u}^{4}3\sigma_{u}^{2}1\pi_{e}^{3}5\sigma_{e}$				102.6	52.8	$2\pi_{u}^{4}4\sigma_{u}^{2}1\pi_{g}^{3}6\sigma_{g}^{1}$
ν Γυ	$4\sigma_{\rm g}1\pi_{\rm u}^43\sigma_{\rm u}^21\pi_{\rm g}^42\pi_{\rm u}^1$		(93-6)	92.3 ^g	104·6	86·1 (0·12) ⁵	$5\sigma_{g}2\pi_{u}^{4}4\sigma_{u}^{2}1\pi_{g}^{4}3\pi_{u}^{1}$
					(non orm)		

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TABLE VIII

 $2\pi^3 7\sigma^2 3\pi^2$ configuration mix with Rydberg ${}^2\Pi$ -states. With SiCl the three lowest excited dublet states given by calculations correspond to the observed transitions. The transition energies are underestimated (by 4 200 to 13 000 cm⁻¹) and the predicted order of the $C^2 \Delta$ and $B^2 \Sigma^-$ states is reversed.

Table IV presents a comparison for the lowest transitions in the linear molecules CCC, SiCC and SiCSi. The transition with $T_0 = 20\,100\,\mathrm{cm^{-1}}$ assigned to SiC₂ was observed in the spectra of N-type stars and under laboratory conditions, in the vapour of silicon carbide. A second transition with $T_0 = 18\,900\,\mathrm{cm^{-1}}$ (trapped in argon) and $T_0 = 19\,300\,\mathrm{cm^{-1}}$ (assignment ambiguous, trapped in neon) was attributed to Si₂C (ref.⁴⁰). A decrease in the transition energy when passing from C₃ to Si₂C (about 6 000 cm⁻¹) is correctly reproduced by the calculation. The transition energy in SiC₂ is predicted to be lower than in Si₂C, whereas the interpretation of experiments tends to favour the reversed order⁴⁰. Anyhow the difference in transition energies between Si₂C and SiC₂ is small, both experimentally and theoretically.

Tables V and VI present a comparison of silicon compounds with carbon and aluminum analogs. The aim of these tables is to show that our parameter set for Si performs equally well as parameter sets suggested previously for other elements, including the recent extension to aluminum. The entries of Table V have already been mentioned in the preceding discussion with the exception of SiH⁺ and CH⁺. The calculated transition energies conform to the experimental finding that there is almost no difference between the two systems. The content of Table V may be summarized in the mean square difference between the observed and calculated transition energies for silicon and carbon compounds, $\langle \Delta \nu \rangle = [1/n \sum (v_i^{\text{obs}} - v_i^{\text{eale}})^2]^{1/2}$. The

two respective values are very close in absolute value, the difference being only 8 per cent in favour of carbon compounds.

When comparing with aluminum compounds we face the problem that aluminum has one valence electron less than silicon. Therefore we either compare transitions between the same states of isoelectronic pairs (SiH^+-AIH, SiO^+-AIO) or we compare singlet states with doublet states in the pairs SiH_2-AIH_2 , AIF-SiF, AICI-SiCI, in which the same critical orbitals are involved in the excitation. Table VI shows the same trends in errors of calculations for silicon and aluminum species, though with the former the errors in absolute value are somewhat larger than with the latter.

Concluding this paragraph we present results for HNSi and SiO₂. Excited states of the HNSi molecule (Table VII) have not been observed so far. Our prediction for the first transition differs largely (by 20 000 cm⁻¹ too low) from the prediction given by *ab initio* calculations²³. This is not due to the Si parameters as the same failure was also found with the HCN molecule. For the latter molecule CNDO/S gives transition energies which are for the ¹ Δ and ¹ Π states too low by 20 000 and 10 000 cm⁻¹, respectively³⁶.

To make the INDO/S prediction for SiO₂ more reliable, we performed the INDO/S calculation for CO₂ as a reference system (Table VIII). The INDO/S calculation reproduces the spectrum of CO₂ remarkably well. Two systems of weak absorptions may be assigned to forbidden ${}^{1}\Delta_{u} \leftarrow {}^{1}\Sigma_{g}^{+}$ and ${}^{1}\Pi_{g} \leftarrow {}^{1}\Sigma_{g}^{+}$ transitions, whereas the strong absorption may be assigned to the allowed ${}^{1}\Sigma_{u}^{+} \leftarrow {}^{1}\Sigma_{g}^{+}$ (f = 1.28) and ${}^{1}\Pi_{u} \leftarrow {}^{1}\Sigma_{g}^{+}$ transitions. The corresponding states in SiO₂ are generally lower in energy. The lowest one, corresponding to a forbidden transition, is predicted to lie at 42 800 cm⁻¹. The allowed ${}^{1}\Sigma_{u}^{+} \leftarrow {}^{1}\Sigma_{g}^{+}$ transition should be much weaker than it is in CO₂ and it should be shifted considerably to lower wavenumbers (by about 30 000 cm⁻¹). The second allowed transition is also to be expected at lower energies, the predicted shift being about 20 000 cm⁻¹.

The Effect of Silyl Substitution and the Introduction of Silicon into Conjugated Systems

This paragraph does not aim at a complete account of the topics of silyl substitution and silicon participation in conjugated systems but its purpose is rather to show a potential usefulness of INDO/S calculations in this field. The results are presented in Tables IX – XII. Phenylsilane was selected as a model system for studying the influence of silyl groups on π -electron systems, whereas silaethylene and silabenzene represent systems containing silicon in the π -electron system. An extreme case is disilylene, which is a conjugated system formed only from silicon atoms. As possible isomers of silaethylene and disilylene, methyl- and silylsilylene as well as silylmethylene have recently been considered^{8,22}. The results for the latter are given in Table XII. Presented in Table XII are also results for the unsubstituted silylene and methylene for the sake of comparison.

In phenylsilane only a slight shift to more positive values was found for the energies of both occupied and vacant orbitals with respect to benzene. There is also a slight increase in the gap between the π orbitals (Table X). This results in a rather small red shift of the first $\pi\pi^*$ transition (Table IX). The experimental results, 37 900 cm⁻¹ for benzene and 36 900 cm⁻¹ for phenylsilane⁴¹, are in agreement with our prediction. Also a small experimentally observed shift of the first ionization potential of benzene on silyl substitutions is reproduced (+0.38 eV for Si(CH₃)₃, see Table X)⁴². In the charge transfer spectra of TCNE complexes with benzenes no effect of silyl substitution was observed⁴³. Moreover, the photoelectron spectrum of vinylsilane⁴⁴ exhibits almost no shift for the first band with respect to ethylene. This findings indicate an almost constant energy of the uppermost π orbital of benzene and ethylene on silyl substitution.

The $B_{2u} \leftarrow A_{1u}$ transition in benzene is predicted to undergo a blue shift of 3 500 cm⁻¹ on silyl substitution. It should be noted that there is a low-lying vacant orbital above -2 eV localized mainly on the substituent (*vide infra*). Electron promotion

TABLE 1X

INDO/S results for $\pi\pi^*$ transition energies in phenylsilane, benzene and silabenzene in comparison to experimental data

I	Phenylsi	lane		Ben	zene			Silabenz	ene	
ΔE^a calc.	f calc.	ΔE^b obs.	state	ΔE calc.	f calc.	ΔE ^c obs.	state	$\Delta E^{e,f}$ calc.	f calc.	ΔE^d obs.
37.6	0.00	36-9	B _{1u}	38.0	0.0	39.5	${}^{1}A_{1}$ ${}^{1}B_{2}$	22·2 30·7	0·11 0·0	31·25 36·8
48.3	0.32		B_{2n}	44.8	0.0	50.5	¹ B ₂	44.0	0.40	47.2
52.4	0.86		E1.	52.5	0.59	56.0	$^{1}A_{1}$	50.4	0.71	
54.9	0.71		. u				•			

^{*a*} A $\sigma\sigma^*$ transition connected with the silylsubstituent is found at 30 500 cm⁻¹ (f = 0.13); ^{*b*} ref.⁴¹, comparable value for benzene 37 900 cm⁻¹; ^{*c*} Experimental values taken from band maxima, ref.⁵⁰; ^{*d*} Argon matrix at 10 K, ref.⁴⁵; ^{*c*} CNDO/CI calculation of H. Bock and B. Roth (unpublished) predicts transition energies of 34 400, 38 400, 51 400 and 52 500 cm⁻¹, ref.⁴⁶; ^{*f*} Further transitions are obtained at 8 700 ($B_1, \pi\sigma^*$), 25 500 ($B_2, \sigma\sigma^*$), 43 200 ($A, \sigma\sigma^*$), 48 700 ($B_1, \pi\sigma^*$) which are connected with the low-lying orbital belonging to Si.

TABLE X

Orbital energies (ε) obtained by INDO/S calculations in phenylsilane, benzene and silabenzene in comparison to experimental ionization potentials (I, in eV)

~	Pheny	Isilane	Benzene	:		Silabenzen	e
Orbitals	мо	ε, calc.	MO ε, calc.	I, obs. ^b	мо	ε, calc.	I, obs. ^c
Vacant orbitals	a", π* a", π* a'	0·28 0·26 - 2·14	b_{1g}, π^* 2.50 e_{2u}, π^* 0.17		a_2, π^* b_1, π^* a_1	0.56 - 0.95 - 2.04	
Occupied orbitals	a", π a' a' a', π	$ \begin{array}{r} - 8.83^{a} \\ - 9.06 \\ - 9.08 \\ - 10.48 \\ - 11.55 \\ \end{array} $	$e_{1g}, \pi - 9.15$ $e_{2g} - 11.80$ $a_{1u}, \pi - 13.53$ $e_{1u} - 15.10$	9·24 11·49 12·1 13·8	b_1, π a_2, π b_2 a_1 b_1, π	$ \begin{array}{r} - & 7 \cdot 02 \\ - & 9 \cdot 08 \\ - & 9 \cdot 29 \\ - & 10 \cdot 35 \\ - & 12 \cdot 31 \end{array} $	8.0 9.3 11.3

^{*a*} Experimental value for $C_6H_5Si(CH_3)_3$ 8.72 eV, comparable value for benzene 9.20 eV, ref.⁴²; ^{*b*} ref.⁴⁷; ^{*c*} ref.⁴⁶.

to this orbital gives rise to a low-lying state (below $\pi\pi^*$ states, at 30 500 cm⁻¹ in phenylsilane) for which no experimental evidence exists. Recently attempts met success to observe silabenzene. As it was expected for a donor substituent, the highest π orbital is lifted by about 1 eV and the $\pi\pi^*$ transitions are shifted bathochromically, the shift being especially large for the lowest transition (from 39 500 in benzene to 31 250 cm⁻¹). These trends are reproduced by the calculations, although the shifts are overestimated by about 1 eV and 9 000 cm⁻¹, respectively. The calculated transition energies at 22 200 and 44 000 cm⁻¹ can be assigned to the observed bands at 31 250 (A_1 , $\pi\pi^*$) and 47 200 cm⁻¹ (B_2 , $\pi\pi^*$), whereas the origin of the band at 36 800 cm⁻¹ is not quite clear because of the zero oscillator strength of the $\pi\pi^*$ transition calculated at 30 700 cm⁻¹.

It may be concluded that our parametrization gives a qualitatively correct account of the participation of silicon in conjugated systems but it reduces the conjugation with neighbouring atoms too much. This becomes even more evident for disilylene. Whereas in silaethylene the occupied π orbital is lifted to -7.4 eV and the transition energy is lowered to 24 100 cm⁻¹, with disilylene our parameter set fails to produce a conjugated π -electron system at all. As a consequence of a too strong upwards

TABLE XI

Passain	T	Vieulailees	Gilaethulana	Disily	/lene ^a
Energies	Туре	vinyishane	Shaethylene	$\beta_0 = -6 \mathrm{eV}$	$\beta_0 = -4 \mathrm{eV}^a$
Orbital energies in eV	vacant occupied	$\begin{array}{rrr} & 0.86\pi^{*} \\ - & 2.19 \ (\text{SiH}_{3}) \\ - & 9.44\pi \\ - & 9.83 \\ - & 10.59 \end{array}$	$\begin{array}{rrr} & 0.67\pi^{*} \\ - & 2.03 \ (\text{SiH}_{2}) \\ - & 7.42\pi \\ - & 10.79 \\ - & 11.11 \end{array}$	$- \frac{1 \cdot 49\pi^*}{2 \cdot 84} (\text{SiH}_2)$ 	$\begin{array}{rrrr} - & 1 \cdot 42\pi^{*} \\ - & 2 \cdot 42\pi^{*} \\ - & 7 \cdot 25 \\ - & 9 \cdot 10 \\ - & 10 \cdot 68 \\ 11 \cdot 80 \end{array}$
$\pi\pi^*$ transi- tion energies in 1 000 cm ⁻¹	singlet triplet	57·1 16·3	24·1 1·3	15·8 0·25	(11·26; 17·47) ^a

INDO/S results for orbital energies and $\pi\pi^*$ transition energies in vinylsilane, silaethylene and disilylene

^{*a*} Using the parameter set proposed in this study ($\beta_0 = -4 \text{ eV}$) no occupied π orbitals are obtained for disilylene. The electronic structure resembles two loosely bound SiH₂ species. See text for details.

	ł	S	iH2	10.000			HC	Н
Quantity	I ype	exp.	calc.	нысн ₃	HIGICH 3	нсын3	calc.	exp.
Orbital energies	vacant		— 1·94 b ₁		2·31 a″ 2·43 a′	- 0.25 a'' - 2.04 a'	- 0.55 b ₁	
ineV	occupied		$- 8.76 a_1$ $-10.24 b_2$	8-38 a' 9-70 a'	7-04 a' 9-48 a'	- 8.76 a' -10.79 a'	$-10.94 \ a_1$ $-15.77 \ b_2$	
Transition energies	singlets	$15.5(T_0)^a$	$23 \cdot 3 {}^{1}B_{1}$ 29 $\cdot 0 {}^{1}A_{2}$	20-9 ¹ <i>A″</i> 26-9 ¹ <i>A″</i>	9.4 ¹ <i>A</i> ″ 25.1 ¹ <i>A</i> ″	9.0 ¹ A″ 36.7 ¹ A″	$16.7 {}^{1}B_{1}$ 58.8 ${}^{1}A_{2}$	$7 \cdot 1^{c}(T_{0})$ 69 · 5 ^c
1000 cm ⁻¹	triplets		12-9 ³ B ₁	11-8 ³ A″	18-7 ¹ A' 6-9 ³ A' 2-6 ³ A'	24.7 $A'- 2.3 A''10.3$ A'	$0.05 \ {}^{3}B_{1}$	-6.84
Energy difference 1 000 cm ⁻¹	${}^{1}B_{1}-{}^{3}B_{1}$	12-0 ⁶	10-4	1.6	2.5	11-3	16.7	14-0 ⁶
Dipole moment 10 ⁻³⁰ Cm		0.33 ⁶	2.07	1.77	9.27	6.40	7-27	5-70 ^b

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shift of the π orbital there is no occupied π -orbital. The electronic structure resembles those of two weakly interacting silvlenes which is indicated by the energies given in Table XI (SiH₂ in Table XII) and the charge distribution. It is known from both ab initio calculations²² and experiment⁴⁸ that the Si=Si bond in disilylene has a double bond character²² with a rotational barrier⁴⁸. If our parametrization is modified in direction of a stronger resonance with silicon $(\beta_{Si}^0 = -4 \rightarrow \beta_{Si}^0 = -6 \text{ eV})$ the occupied π orbital is found at -6.0 eV (*ab initio*: -6.7 eV^{22}) and the excitation energy becomes $16\,100\,\mathrm{cm}^{-1}$. The bond order for the Si=Si bond (1.87) is only slightly smaller than it is in silaethylene (1.94). We believe, however, that the results for disilylene are actually in favour of our parametrization. Namely, according to ab initio calculations mentioned above the proper ground state of the Si_2H_4 system is singlet silylsilylene²². Assuming this system, the INDO treatment gave a good account of the observed facts. The energies of the occupied orbitals are seen in Table XII to be in fair agreement with the *ab initio* results²² (-7.8 and -10.4 eV). Even such a subtle problem as determination of the nature of the ground state was correctly accounted for. Ab initio calculations predicted the ${}^{3}A''$ triplet state of this system to lie 3 900 cm⁻¹ above the singlet ground state²². INDO/S gives for this energy difference $6\,900\,\mathrm{cm}^{-1}$.

Table XII also comprises results for silvlmethylene and methylsilylene which are isomers of silaethylene. According to the prediction of ab initio calculations8 methylsilvlene is more stable than silaethylene. To begin with discussing Table XII we would like to point out the capability of the present INDO/S method of giving a good account of the difference in the electronic structure between silvlene and methylene (transition energy, ${}^{1}B_{1} - {}^{3}B_{1}$ energy difference, dipole moment). Even the trend in the energy difference between the lowest triplet state and the lowest singlet state is correctly predicted. On the basis of our calculations we predict methyland silvlsilvlene to have singlet ground states and silvlmethylene to have a triplet ground state. Exactly this has been given by ab initio calculations^{8,22}. If we use the trends in our calculated values for the extrapolation of experimental excitation energies of silvlene and methylene to HSiSiH₃ and HCSiH₃, we may expect very low excitation energies in the infrared region for HSiSiH₃ and HCSiH₃ and a transition near 13 000 cm⁻¹ for HSiCH₃. The latter value is of some significance for the discussion of the experiments by Drahnak, Michl and West⁴⁹ who assigned an excited state observed at 18 700 cm⁻¹ (T_0 value) to Si(CH₃)₂. According to our calculations we would expect a transition energy in Si(CH₃)₂ to be lower than in HSiCH₃, *i.e.* below 13 000 cm⁻¹.

As with phenylsilane, a low-lying vacant orbital, which is due to the silyl substitution, is also found with silylsilylene and silylmethylene. This orbital is involved in ${}^{1}A'$ and ${}^{3}A'$ transitions (at 18 700 and 24 700 and 2 600 and 10 300 cm⁻¹, respectively). Concluding this paragraph, we believe that INDO/S with parameters for silicon provides a reasonable explanation for the known experimental facts and we hope that it will be of some help in identifying new silicon-organic species.

Note added in proof: After the completion of our manuscript the results of *ab initio* calculations on SiS excited states became available (J. M. Robbe, H. Lefebre-Brion, R. A. Gottscho: J. Mol. Spectr. 85, 215 (1981)). The calculated excitation energies are the following (in 10^3 cm^{-1} , experimental values in parenthesis): $X^1\Sigma^+ 0.0$ (0.0), $C^1\Sigma^- 29.4$ (29-1), D^1A 29-7 (28-9), $A^1\Pi$ 38-1 (35-0), $E^1\Sigma^+$ 48-0 (41-9).

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Translated by the author (P. Č.).

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